Plasma and Dry Micro/Nanotechnologies 5. Electrical Discharges

Lenka Zajíčková

Faculty of Science, Masaryk University, Brno & Central European Institute of Technology - CEITEC

lenkaz@physics.muni.cz

spring semester 2023



Central European Institute of Technology BRNO | CZECH REPUBLIC





5 Classification of Electrical Discharges

Various classification of discharges:

according to pressure

- Iow pressure
- atmospheric pressure

 \Rightarrow importance of mean free path

 $\lambda = 1/(n_{\rm g}\sigma)$

 $n_{\rm g}$ is gas density, σ is collisional cross section and its comparison to Debye length $\lambda_{\rm D}$ and plasma reactor dimensions

according to frequency

- d.c.
- low frequency (50 Hz, audio range, low radio frequency up to 1 MHz)
- high frequency (typically 13.56 MHz)
- microwave (typically 2.45 GHz)

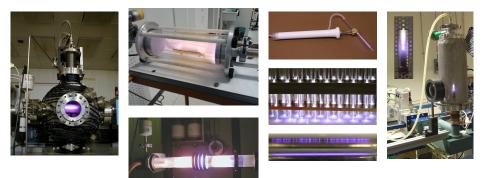
 \Rightarrow importance of electron and ion plasma frequencies

$$\omega_{\mathrm{pe,i}} = \sqrt{\frac{e^2 n_{\mathrm{e}}}{\varepsilon_0 m_{\mathrm{e,i}}}}$$

and their comparison to discharge frequency

Types of Discharges

- d.c. d.c. glow discharge or planar diode, d.c. magnetron, vacuum arc
- Iow frequency (50 Hz, audio range, low radio frequency up to 1 MHz) low pressure planar diode, atmospheric pressure dielectric barrier discharge, glide arc, plasma jet
- high frequency (typically 13.56 MHz) low pressure capacitively or inductively coupled discharges
- microwave (typically 2.45 GHz) low pressure resonator, surface wave, atmospheric pressure plasma torch

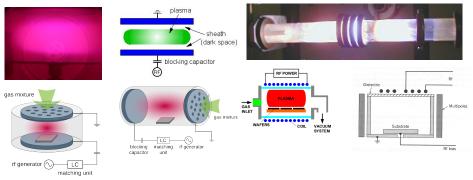


Low Pressure RF Discharges

radio frequency (13.56 MHz)

capacitively coupled (CCP) discharge

inductively coupled (ICP) discharge



sustained by r.f. current and voltage coupled via capacitive plasma sheath

Atmospheric Pressure Discharges

▶ parallel plate electrodes - low frequency (≈ few kHz) dielectric barrier discharge (DBD)

filamentary

homogeneous

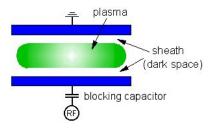


plasma jets

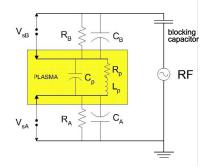
wide variety of frequencies (50 Hz gliding arc jet – 13.56 MHz plasma jet), configurations, working gases \Rightarrow variations of gas temperature, active species, area

5.1 Low Pressure Capacitively Coupled Plasma

Radio frequency discharges (typically 13.56 MHz) sustained by r.f. current and voltage coupled via capacitive plasma sheath are capacitively coupled plasma (CCP).







CCPs belong to **glow discharges** (discharges with high voltage cathode sheath - electrons originate by secondary emission from the cathode).

Capacitively Coupled Plasma - D.C. Self Bias

- External electrical circuit usually contains "blocking" capacitor, i. e. dc current cannot flow
- Most CCPs are asymmetric $\textit{A}_{\rm sA} \neq \textit{A}_{\rm sB}$

 \Rightarrow plasma acts as a voltage divider due to equal displacement currents through both the plasma sheaths:

$$\frac{V_{\rm sB}}{V_{\rm sA}} = \left(\frac{A_{\rm sA}}{A_{\rm sB}}\right)^q$$

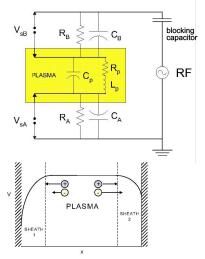
An easily measurable **d.c. self bias** is set up between RF electrode and the ground

$$U_{\rm bias} = -(V_{\rm sB} - V_{\rm sA})$$

which is negative in the usual case of smaller RF electrode, i.e. $V_{\rm sB}>V_{\rm sA}.$

 \Rightarrow lons are accelerated in high-voltage sheath at (smaller) RF electrode. Sheath voltage is proportional to RF voltage, i. e. RF power.

If ions do not collide in the sheath (at low pressure of few Pa) they hit the surface with high energy of several 100 V.



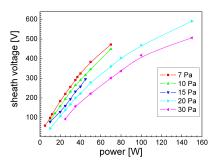
8/35

Capacitively Coupled Plasma - Energy of lons

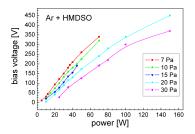
Example for Ar + hexamethyldisiloxane (HMDSO) CCP at 13.56 MHz:

- Ar + HMDSO 1:1 mixture
- total flow rate 6 sccm
- pressure p 7–30 Pa
- power W 5–150 W

 \Rightarrow Sheath voltage at RF electrode $V_{\rm sB} = 0.39 V_0 + 0.73 U_{\rm bias}$

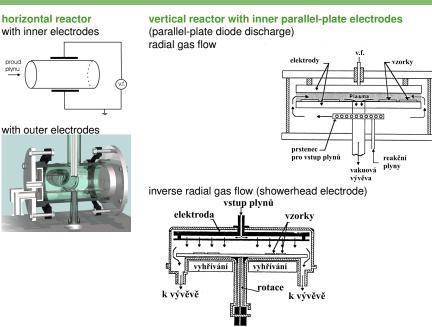


 dc bias-voltage at RF electrode U_b varied with W and p



E. Kedroňová et al. Plasma Process. Polym. 12 (2015) 1231

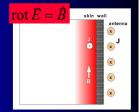
Construction of CCP Reactors



Principle of ICP discharges

r.f. antenna in the form of coil attached to dielectric window – electromagnet creating rf mg field – induction of rf el field

Energy of electrical field is transferred to the electrons in thin "skin" layer. > non-collisional processes – electrons "collide" with induced oscilating el. field > energy is dissipated by collisional (ohmic) processes

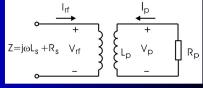


skin depth (collisionless)

 $\delta_s = \delta_c \equiv c \, / \, \omega_p$

 non-capacitive coupling is a key point for low voltages (typically 20-30 V) in sheaths at electrodes and reactor walls

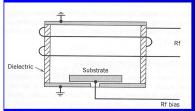
Farraday shielding is used to surpress capacitive coupling (high voltage on the coil)



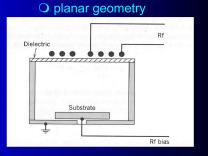


Construction of ICP reactors

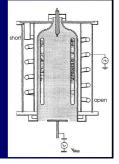
O cylindrical geometry





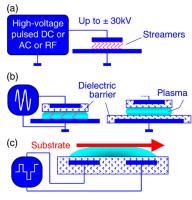


O helical resonator

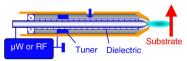


5.2 Cold Atmospheric Pressure Discharges

Plate-to-plate configuration



Plasma jet configuration



L. Bárdos, H. Baránková, Thin Solid Films

At low p, the collision frequency is low \Rightarrow electron energies remain high compared to ion neutral energies \Rightarrow non-equilibrium (cold) plasma.

At high p, the collision frequency is high \Rightarrow plasma tends to equilibrate temperatures \Rightarrow formation of streamers (fast-moving ionization fronts in the form of filaments) - **precursors of sparks** (hot plasmas)

Suppression of sparks using:

- high-frequency AC fields or short-pulsed DC power
- dielectric barriers on AC electrodes
- high gas flow rates
- special electrode shapes with multiple structures
- suitable gas, e.g. He.

5.2 Atmospheric Pressure DBD (AP-DBD)

Two forms of dielectric barrier discharges (DBDs) with parallel plate electrodes:

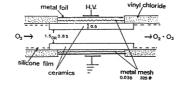
- filamentary
- homogeneous



Stabilization of homogeneous DBDs requires suppression of filament formation.

Important role of

- structure and material of electrodes e.g. M. Kogoma, S. Okazaki, JPD (1994) 27 1985
- higher frequencies of power supply
 T. Nozaki et al., Plasma Process. Polym. (2008) 5 300)
- gas mixture (He, Ne, N₂, Ar + NH₃ etc.):

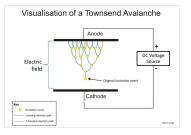


- homogeneous DBD in He, Ar/NH₃ and N₂ F. Massines et al. Surf. Coat. Technol. 174–175, 8 (2003); Plasma Phys. Controlled Fusion 47, B577 (2005).
- PECVD in HMDSO/N₂ and HMDSO/N₂/synthetic air mixtures D. Trunec et al. J. Phys. D: Appl. Phys. 37 (2004) 2112; J. Phys. D: Appl. Phys. 43 (2010) 225403
- PECVD in Ar/C₂H₂
 M. Eliáš et al. J. Appl. Phys. 117(10) (2015) 103301

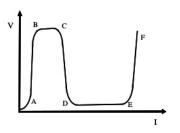
Homogeneous Dielectric Barrier Discharges

Two different forms of homogeneous discharges were classified by Massines et al. Both start with Townsend breakdown initiating a Townsend discharge but

- ▶ in He, during the current increase, the discharge transits to a glow discharge $(n_e \approx 10^{11} \text{ cm}^{-3})$ having a cathode fall and a positive column if gas gap is > 2 mm atmospheric pressure glow discharge (APGD)
- ▶ in N₂, the ionization level is too low ($n_e \approx 10^8 \text{ cm}^{-3}$) to allow formation of cathode fall. Localization of the electrical field and the glow regime cannot be achieved
 - atm. pressure Townsend discharge (APTD).



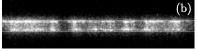
- (A) region of non-self-sustaining discharge
- (BC) Townsend discharge



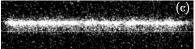
- (CD) subnormal glow discharge
- (DE) normal glow discharge
- (EF) abnormal glow discharge



filamentary DBD in Ar/CH₄



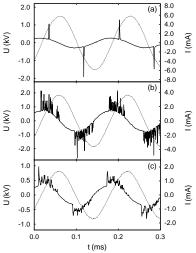
homogeneous DBD in Ar/C₂H₂



(80 μ s (one half-period) exposure time)

- difference caused by possibility of Penning ionization of C₂H₂ in Ar
- Ar 1s⁵ metastable 11.55 eV,
- C₂H₂ ionization potential 11.40 eV but CH₄ 12.61 eV

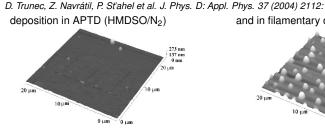
M. Eliáš et al., J. Appl. Phys. 117(10) (2015) 103301



DBD (a) DBD in pure Ar, (b) DBD in Ar/CH₄, (c) APGD in Ar/C₂H₂

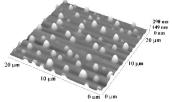
Why to Use Homogeneous DBD for Deposition?

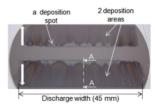
to eliminate unwanted surface structures and non-uniformities



H. Caquineau et. al J. Phys. D: Appl. Phys. 42 (2009) 125201: Local increased of the deposition rate, "deposition spots", due to non-uniform power dissipation in micro-filaments:

and in filamentary discharge





to modify temperature sensitive polymer substrates and polymer nanofibers

17/35

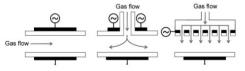
Problem of Film Uniformity

Amospheric-pressure plasmas are characterized by high collision frequencies of particles (several orders of magnitude higher compared to low pressure)

 \Rightarrow Delivery of active species to the substrate is much more advection than diffusion-driven (opposed to low-pressure).

 \Rightarrow High electron-neutral collision frequency \Rightarrow fast monomer conversion

Basic gas delivery set-ups

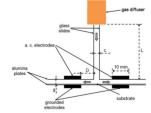


are modified for optimization of flow patterns by gas dynamics simulations

P. Cools et al., Plasma Process. Polym. 2015, 12, 1153–1163

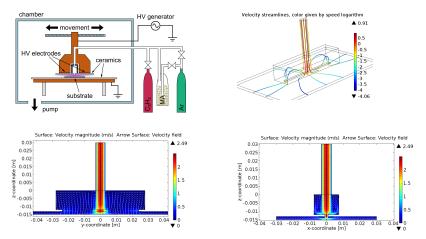


H. Caquineau et al. J. Phys. D: Appl. Phys. 42 (2009) 125201



Gas Dynamics Simulations in Our Set-up

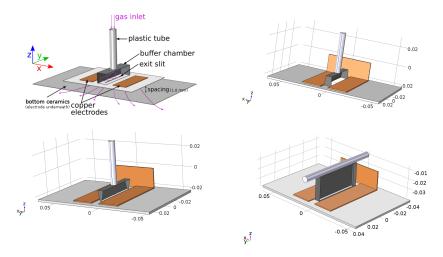
Solving the Navier-Stokes equations (laminar flow) in full 3D geometry for pure Ar (results are shown for 1550 sccm):



 \Rightarrow Complex flow patterns inside the buffer chamber make the flow through the slit relatively even but better designs of the buffer chamber can be found!

Gas Supply Optimization Using CFD Model

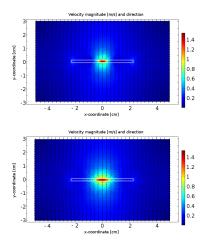
Variations of four different geometries tested

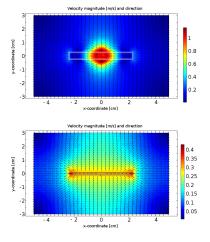


L. Zajíčková et al. Plasma Physics and Controlled Fusion 59(3) (2017) 034003

Gas Supply Optimization Using CFD Model

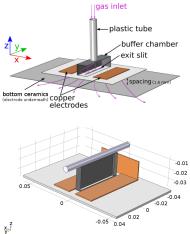
Variations of four different geometries tested



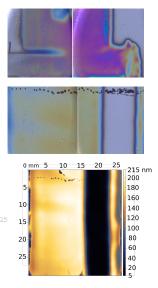


Does It Work in Real Life?

(case study for DBD co-polymerization of MA and C_2H_2 in Ar, no electrode movement)

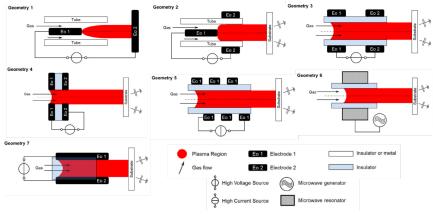


Interference colours are measured by imaging spectroscopy refractometry \Rightarrow fitting of optical data provides spatially resolved film thickness



5.3 Atmospheric Pressure Plasma Jets

- ▶ operating in local thermal equilibrium (LTE) $T_{\rm e} \sim T_{\rm n}$, $n_{\rm e} \ge 10^{15}$ cm⁻³ transferred arc (torch), plasmatron
- ► translational plasmas (non-LTE but with a significant heating of the background gas $T_n \sim$ several thousand Kelvin gliding arc, expanding sparks, non-transferred arc
- ▶ non-LTE "cold" plasma jets $T_{
 m e} \gg T_{
 m n}, T_{
 m n} = 300 1000$ K, $n_{
 m e} < 10^{13}$ cm⁻³



J. Winter at al. Plasma Sources Sci. Technol. 24 (2015) 064001

5.4 Arc-Based Atmospheric Pressure Plasma Jets

Plasma jets:

- ▶ operating in local thermal equilibrium (LTE) $T_{\rm e} \sim T_{\rm n}$, $n_{\rm e} \ge 10^{15}$ cm⁻³ transferred arc (torch), plasmatron
- ► translational plasmas (non-LTE but with a significant heating of the background gas) $T_n \sim$ several thousand Kelvin gliding arc, expanding sparks, non-transferred arc
- ▶ non-LTE "cold" plasma jets $T_{
 m e} \gg T_{
 m n}$, $T_{
 m n} = 300 1000$ K, $n_{
 m e} < 10^{13}$ cm⁻³

J. Winter at al. Plasma Sources Sci. Technol. 24 (2015) 064001

Industrial plasma jets based on arc:

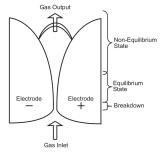
- Sura Instruments, non-transferred arc (patent WO 2015/107059 A1), dc or low f, argon flow, precursors for deposition
- PlasmaTreat, non-transferred arc (DE10223865 A1, US2002179575, DE102008058783 A1), 1-100 kHz, air flow, plasma cleaning, activation, deposition



... and some others

Gliding Arc

A. Fridman, Plasma Chemistry, Cambridge University Press 2008



The glide arc can be operated in the **transitional regime** (combines the benefits of both equilibrium and non-equilibrium discharges):

- the discharge starts thermal
- becomes non-thermal during the space-time evolution



f = 50 Hzmax. P = 500 W, max. U = 10 kV





typical operation conditions: 500 W, 10 kV, (dry) air 11.8 slm

25 / 35

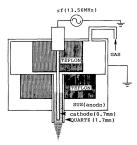
5.5 RF Plasma Jets

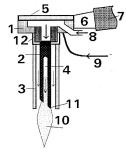
"Cold" plasmas required for surface modification of thermosensitive materials (bonding, painting, printing) or plasma medicine/agriculture

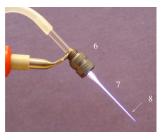
Non-LTE atmospheric pressure plasma jets need to prevent the transition to arc \Rightarrow pulsed or high *f* discharges, a dielectric barrier at one or both the electrodes

Earliest cold RF plasma jet proposed by Koinuma et al.

Development of cold RF jets in Brno, Masaryk University







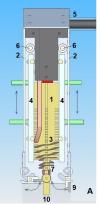
APL 60 (1992) 816

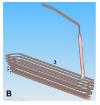
M. Klíma et al. Czech Patent PV147698 (1998), US6,525,481 (2003) J. Janča et al. Surf. Coat. Technol. 116–119 (1999) 547

26 / 35

RF Plasma Slit Jet

In Brno, we developed a new type of RF plasma jet. Unlike other jets working with capacitive coupling (*E* component important) it should generate EM with both the components (*E*, *H*) high (according to preliminary EM field calculations $E_{max} = 10^5$ V/m, $H_{max} = 800$ A/m).







RF plasma slit jet is successfully constructed with the width of 15 or 30 cm.

typical operating conditions: 300-600 W, 50–100 slm of Ar, 0-4 slm of N_2

The jet accommodates periodic structures consisting of varying combinations of inductors with specially designed geometry and winding - matching is an integral part.